Please amend the subject application as follows:

IN THE CLAIMS:

Please accept amended claims 1, 4, 5, 10, 13, and 17-19 as follows:

1. (currently amended) A method for overlay measurement using a multiplex filter, comprising:

selecting a first filter from a plurality of filters and positioning the first filter underneath a lens of an overlay measurement apparatus;

determining whether overlay marks formed on a wafer are perceptible through the lens and the first filter;

measuring the overlay marks if the overlay marks are perceptible; [[and]]

replacing the first filter with a second filter from the plurality of filters if the overlay marks are not perceptible through the first filter; and

stopping the method and making an error determination after failing to perceive the overlay marks through a predetermined number of filters.

2. (original) The method of claim 1, further comprising:

determining whether the overlay marks are perceptible through the lens and the second filter; and

measuring the overlay marks if the overlay marks are perceptible through the second filter.

3. (original) The method of claim 1, further comprising:

analyzing measured values of the overlay marks;

calculating results of the analysis of the measured values; and

feeding calculated data into the overlay measurement apparatus.

4. (currently amended) The method of claim 1, ~~further comprising:~~

~~stopping the method if the overlay marks are not perceptible through each filter from~~ wherein the predetermined number is equal to the total number of the plurality of filters.

5. (currently amended) The method of claim 1, wherein the predetermined number is equal to less than the total number of the plurality of filters ~~include at least three filters~~.

6. (original) The method of claim 1, wherein the plurality of filters includes a yellow filter, a green filter and a red filter.

7. (original) The method of claim 6, wherein the first filter is the yellow filter.

8. (original) The method of claim 6, wherein the second filter is one of the green filter and the red filter.

9. (original) The method of claim 1, further comprising replacing the second filter with

a third filter from the plurality of filters if the overlay marks are not perceptible through the second filter.

10. (currently amended) The method of claim 1, further comprising continuously replacing each of successive replacement filters with an unused filter from the plurality of filters until the overlay marks are perceptible through one of the replacement filters or ~~each one of~~ the ~~plurality~~ predetermined number of filters has been used.

11. (original) The method of claim 1, wherein the multiplex filter includes the plurality of filters positioned thereon and the step of replacing is performed by rotating the multiplex filter.

12. (original) The method of claim 1, wherein the step of replacing is performed automatically.

13. (currently amended) A method for overlay measurement, comprising:

selecting a first filter from a plurality of filters and positioning the first filter on an overlay measurement apparatus;

determining whether overlay marks formed on a semiconductor surface are able to be measured using the first filter;

measuring the overlay marks if the overlay marks are able to be measured; [[and]]

replacing the first filter with a second filter from the plurality of filters if the overlay marks are not able to be measured using the first filter; and

stopping the method and making an error determination after failing to measure the overlay marks using a predetermined number of filters.

14. (original) The method of claim 13, further comprising:

determining whether the overlay marks are able to be measured using the second filter; and

measuring the overlay marks if the overlay marks are able to be measured using the second filter.

15. (original) The method of claim 13, wherein the plurality of filters includes a yellow filter, a green filter and a red filter.

16. (original) The method of claim 13, further comprising replacing the second filter with a third filter from the plurality of filters if the overlay marks are not able to be measured using the second filter.

17. (currently amended) The method of claim 13, further comprising continuously replacing each of successive replacement filters with an unused filter from the plurality of filters until the overlay marks are able to be measured using one of the replacement filters or ~~each one of~~ the predetermined number of the plurality of filters has been used.

18. (currently amended) The method of claim 13, wherein the step of replacing is performed by automatic rotation of a multiplex filter including the plurality of filters.

19. (currently amended) A method for overlay measurement, comprising:

using a plurality of filters in conjunction with an overlay measurement apparatus to perceive overlay marks on a semiconductor surface; [[and]]

measuring perceptible overlay marks; and

stopping the method and making an error determination after failing to perceive the overlay marks through a predetermined number of filters.

20. (original) The method of claim 19, wherein each filter of the plurality of filters is alternately positioned in line with a lens of the overlay measurement apparatus.